

ISSUE CLASSIFICATION	
Class	Subclass

PATENT NUMBER

U.S. UTILITY Patent Application

<p>771 O.I.P.E.</p> <p>SCANNED <u>HKM</u> (3) O.A. <u>SP 3</u></p>	PATENT DATE
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APPLICATION NO. 09/820694	CONT/PRIOR	CLASS 438	SUBCLASS	ART UNIT 2812	EXAMINER
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APPLICANTS

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TITLE

Method of plasma etching silicon nitride

PTD-2040
12/99

ISSUING CLASSIFICATION												
ORIGINAL		CROSS REFERENCE(S)										
CLASS		SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)								
INTERNATIONAL CLASSIFICATION												

☐ Continued on Issue Slip Inside File Jacket

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS		CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)		NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)		ISSUE FEE	
			Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)		ISSUE BATCH NUMBER	
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